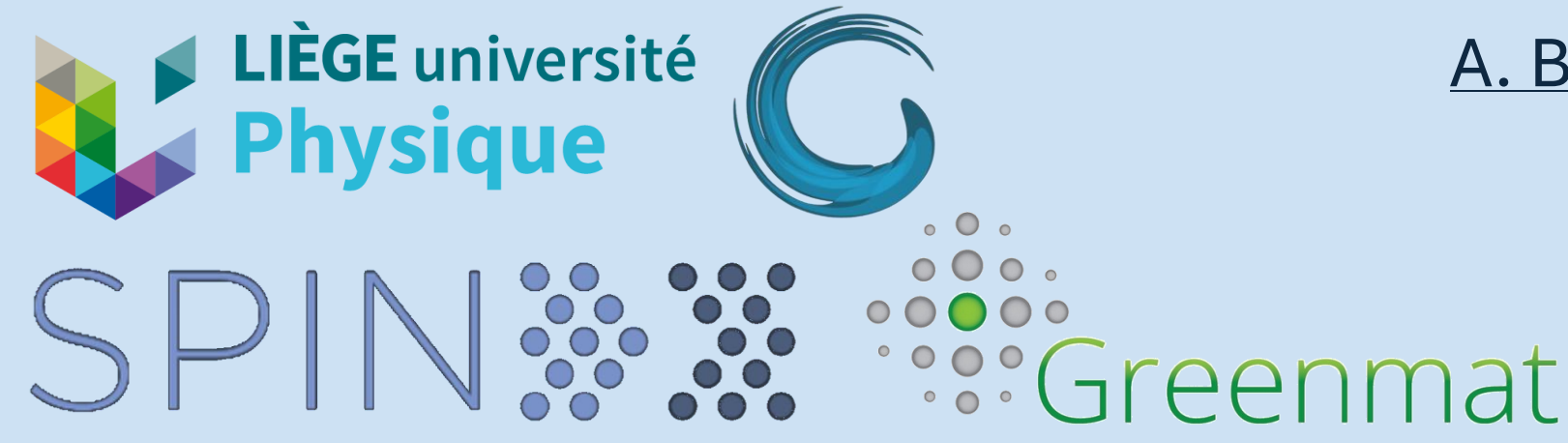


Crystalline phase transitions and point defects in nitrogen and magnesium-doped copper oxide thin films deposited by magnetron sputtering under optimized pressure conditions



A. Baret^{1,*}, T. Ratz¹, E. Fourneau², N. Sliti¹, C. Malherbe³, B. Vertruyen⁴, A. V. Silhanek², N. D. Nguyen¹

¹ Université de Liège, Département de Physique, CESAM/SPIN, B-4000 Liège, Belgium

² Université de Liège, Département de Physique, CESAM/EPNM, B-4000 Liège, Belgium

³ MOLSYS, Department of Chemistry, Université de Liège, Belgium

⁴ GREENMAT, Department of Chemistry, Université de Liège, Belgium

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abaret@uliege.be



Abstract

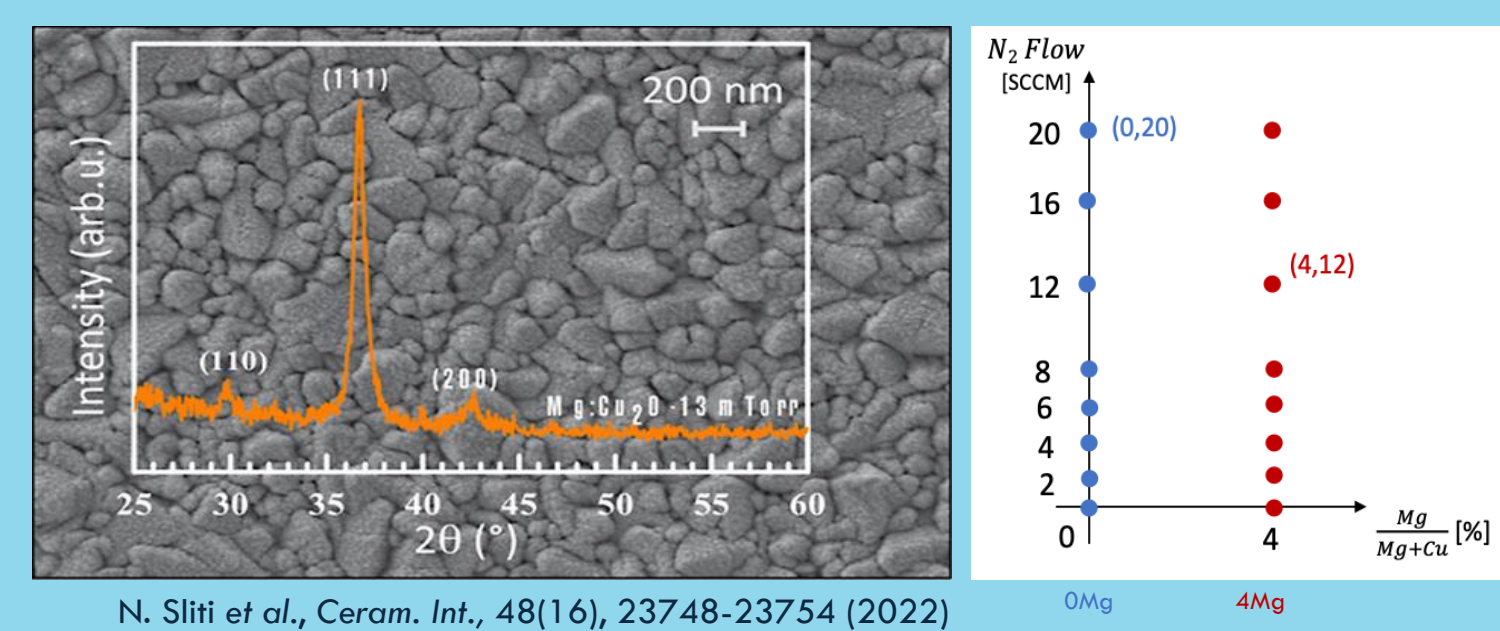
Cu₂O is a promising transparent conducting oxide for photovoltaic applications, with a large absorption coefficient and *p*-type conductivity. Additionally, this material is abundant and nontoxic and can be synthesized using various chemical and physical routes [1]. The objective of this work is to extend the understanding of the role of point defects in intentionally doped copper oxide thin films. Moreover, this work contributes to the assessment of Mg and N as doping species through extensive material characterization including X-ray and Raman spectroscopy measurements.

RF-sputtering



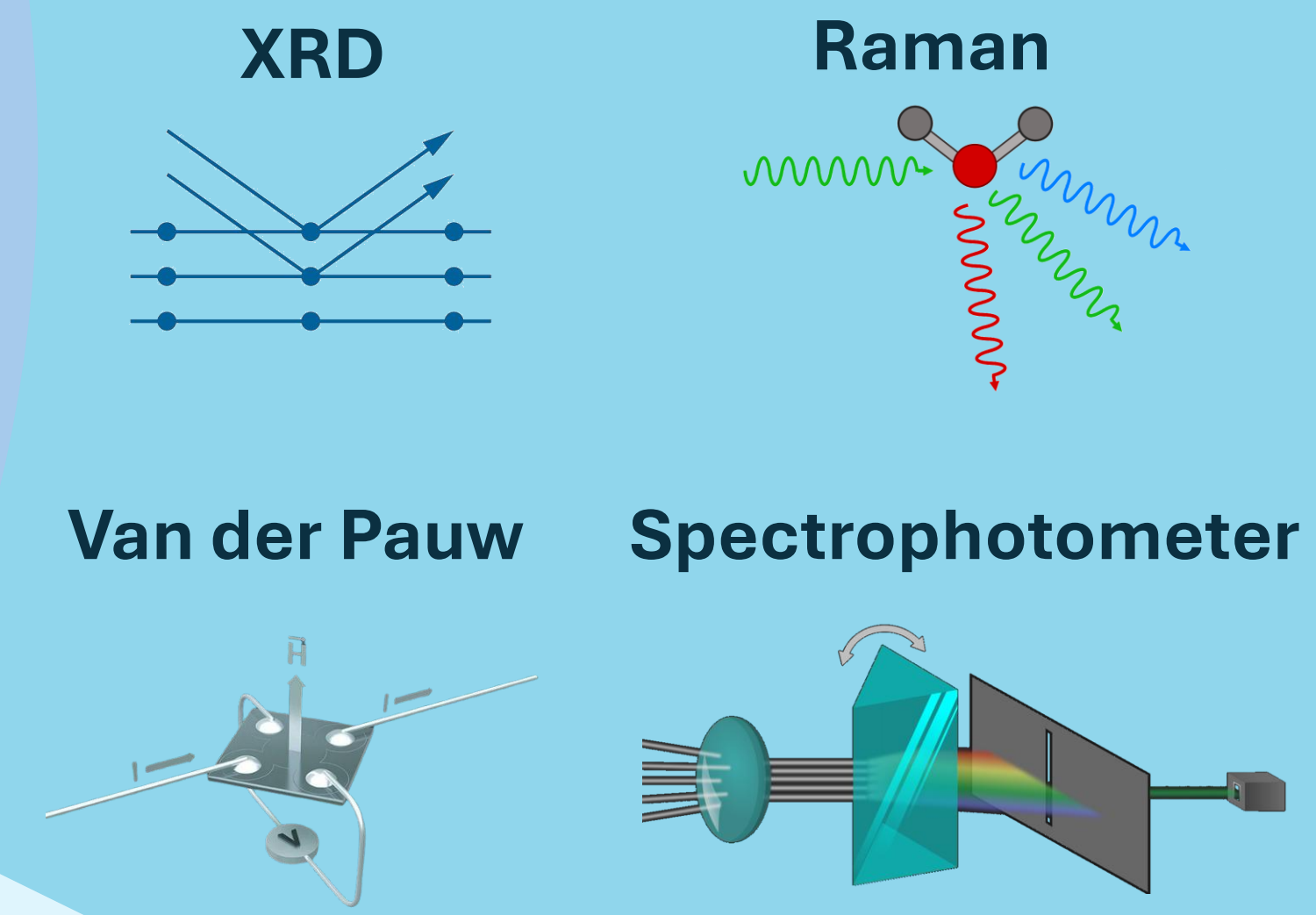
2-inch targets : CuO (0Mg) and Cu₂O:Mg (4Mg)
Ar plasma (power 70 W, pressure 5 mTorr, flow 20 sccm)
No substrate heating, dopant flow : N₂ [0; 20] cm

Cu₂O thin film



N. Sliti et al., Ceram. Int., 48(16), 23748-23754 (2022)

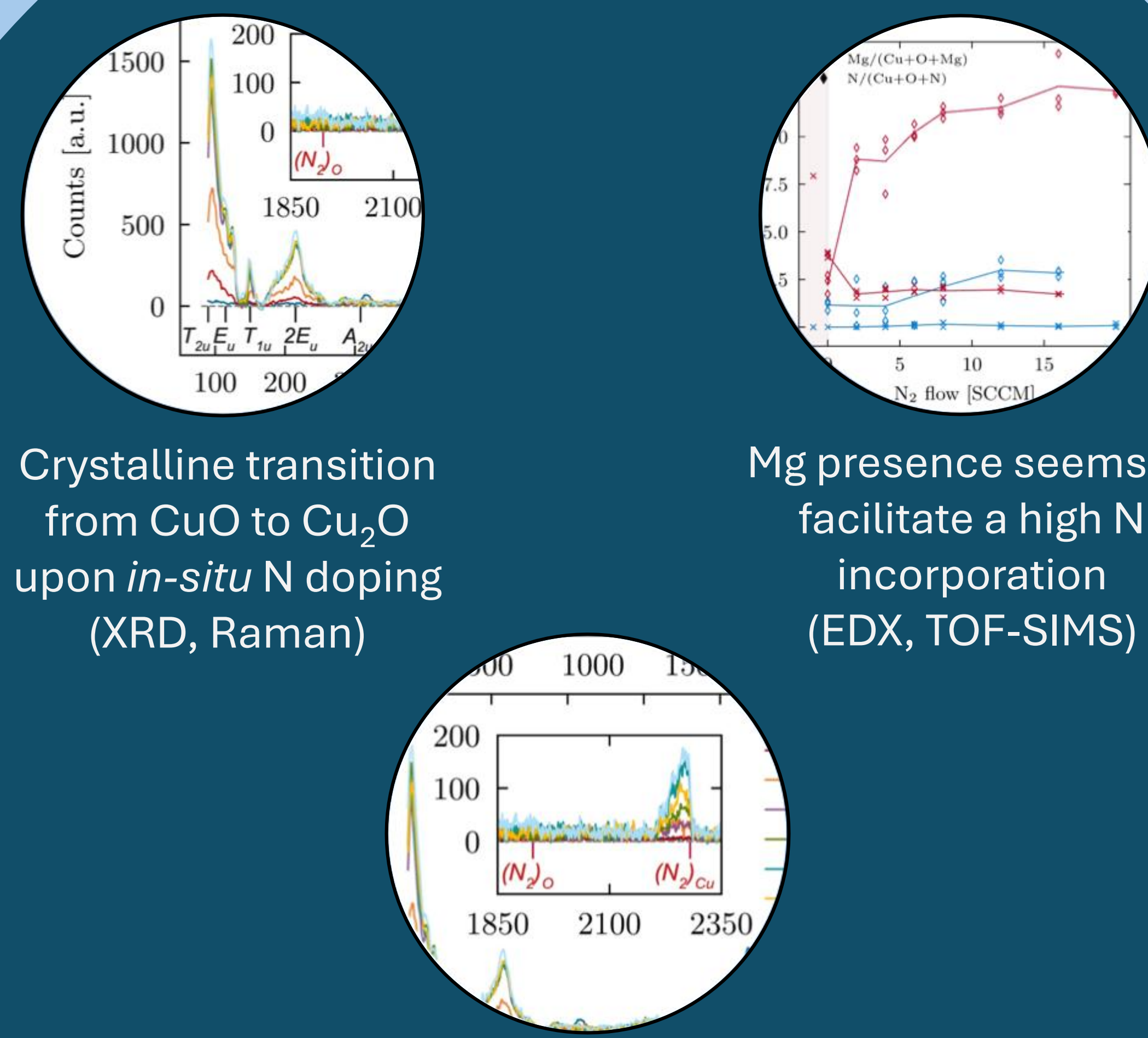
Measurements



[2-4]

Introduction

Key takeaways



Crystalline transition from CuO to Cu₂O upon *in-situ* N doping (XRD, Raman)

Mg presence seems to facilitate a high N incorporation (EDX, TOF-SIMS)

(N₂)Cu shallow acceptor point defect Raman activity proportional to N₂ deposition flow (Raman)

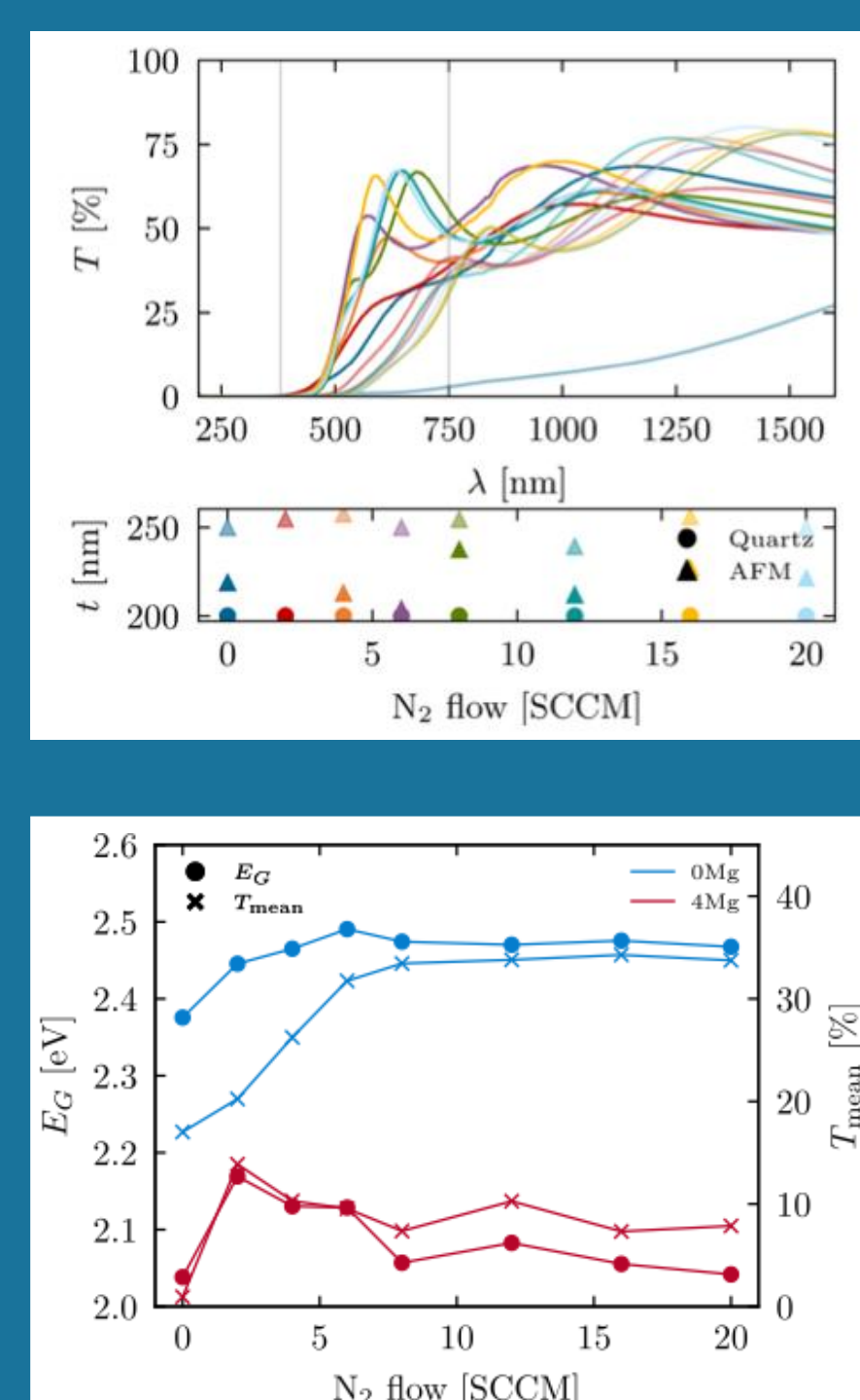
Methods

Properties

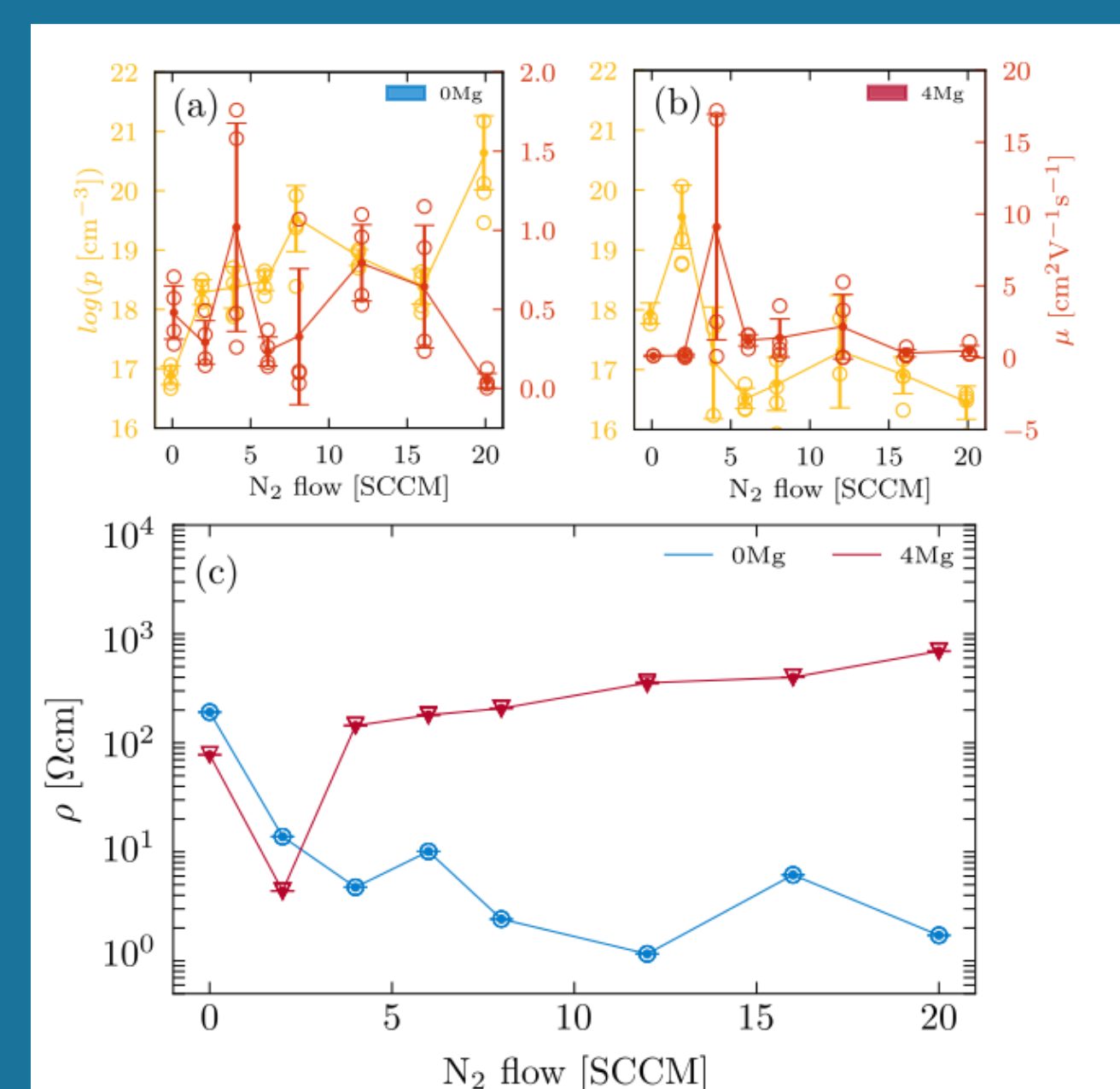
Conclusions

In summary

Optical

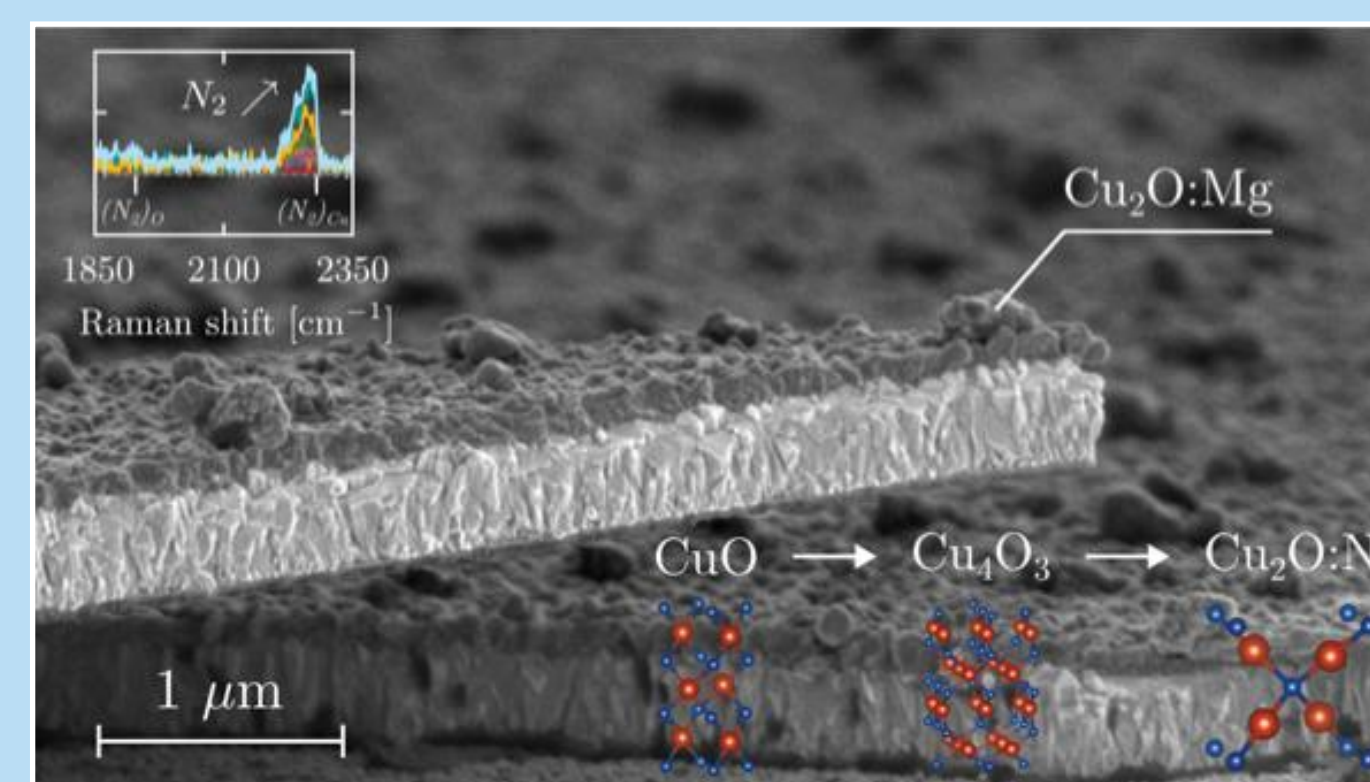


Electrical



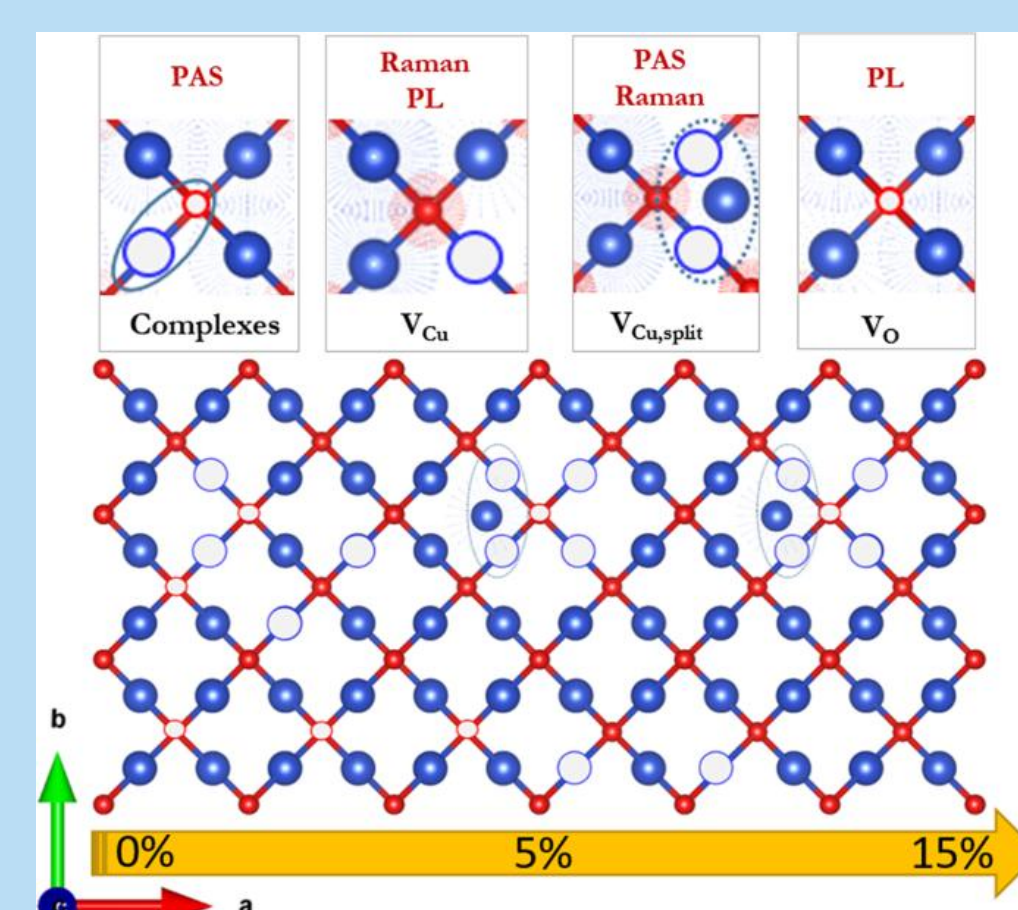
- ➔ *P*-type conductivity, with **resistivity decreasing** by up to 2 orders of magnitude upon **N doping** due to **higher carrier concentrations**.
- ➔ *N*-doping **enhances film transmittance**. *N*-incorporation on O site was not observed, *i.e.* **absence** of N_O defect.

Key role of XRD in this study



T. Ratz et al., ACS Appl. Electron. Mater. 7 (2), 643–651 (2025)

Perspectives



[5]

- **Monodoping** copper oxide with N or Mg leads to **enhanced** opto-electrical properties
- (N,Mg) **co-doping** induces **degraded** opto-electrical characteristics
- Identification of (N₂)Cu defect as **shallow** acceptor
- **High level of N incorporation** is associated with **lower film quality** and **amorphization**

- Control of the **O** flow during the thin film synthesis to better control **defects**
- **Photoluminescence** and advanced measurements such as Positron Annihilation Spectroscopy (PAS)

References

- [1] B. Meyer et al., physica status solidi (b), 249, 1487–1509 (2012).
- [2] What is Raman Spectroscopy? Raman Spectroscopy Principles, Edinst (2021).
- [3] The difference between spectroscopy, spectrometer and spectrophotometer, Silicann (2020).
- [4] Use Hall Effect Measurements for the Characterization of New and Existing Materials, Tektronix (2017).
- [5] A. Sekkat et al., Nat. Com., 13.1 (2022): 5322.

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Acknowledgments

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